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## Supplementary information

## Ni/NiO/C hollow microspheres fabricated by Mist-CVD process

## with assistance of ethanolamine: An efficient OER catalyst

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## **Supplementary Figures and Table**

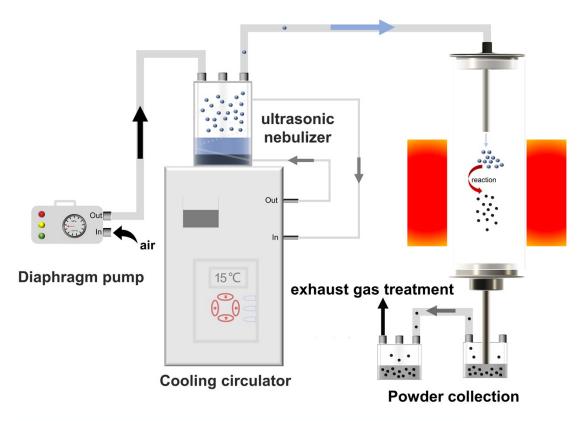


Fig. S1 The schematic illustration of Mist-CVD for the fabrication of electrocatalysts.

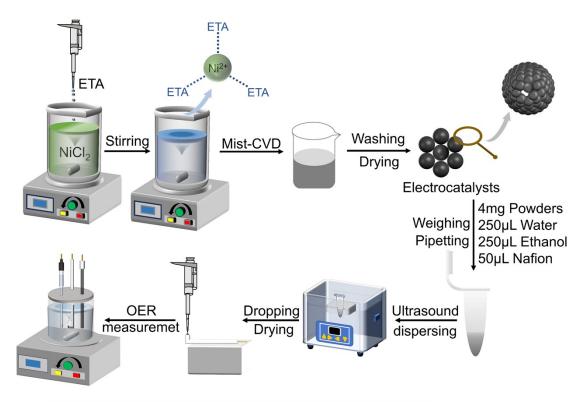


Fig. S2 Flowchart of fabrication and OER measurement of electrocatalysts.

Sample	$\eta_{10}$	Tafel slope	$C_{ m dl}$	ECSA	$R_{ m ct}$	TOF
	(mV)	$(mV dec^{-1})$	$(\mu F \text{ cm}^{-2})$	$(cm^{-2})$	$(\Omega)$	$(S^{-1})$
Ni-400	386.0	117.0	223.2	5.58	1.08	0.0022
Ni-600	286.4	54.8	277.0	6.93	0.23	0.0492
Ni-800	350.7	89.3	246.7	6.17	0.37	0.0039
Ni-1000	382.5	91.5	231.8	5.80	0.84	0.0014
RuO <sub>2</sub>	121.7	122.7	471.9	11.80	60.76	0.0382

Table S1 Parameters of OER performance of the electrocatalysts.

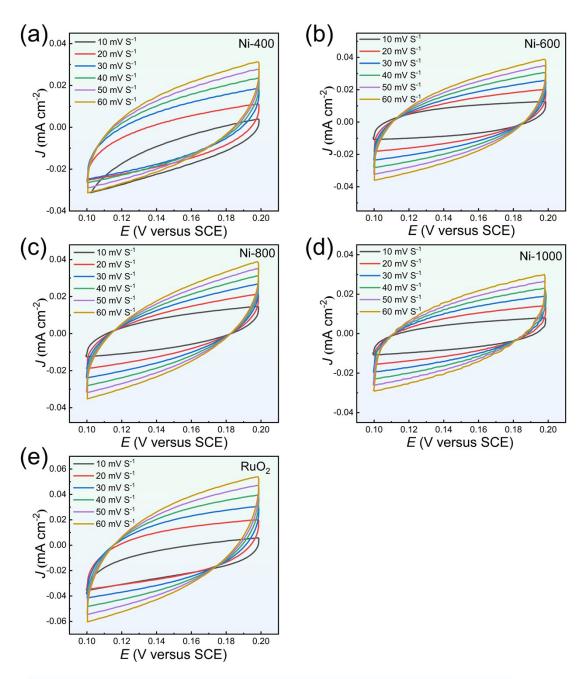


Fig. S3 CV curves of the as-prepared electrocatalysts at different scan rates without

the Faradaic process.